Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1.-5. (Cancelled)

6. (Currently Amended) A process for the preparation of phosphonic estermodified organosiloxanes of the formula

$$(R_2SiO_{2/2})_p(R_3SiO_{1/2})_q[O_{1/2}H]_t[(O_{f/2}R^1_{3-f}SiCR^2_2P(O)(OR^4)_2]_s$$
 (I),

in which

- is a hydrogen atom or a monovalent, optionally -CN-, -NCO-, NR^5_2 -, -COOH-, -COOR⁵-, -halogen-, -acryloyl-, -epoxy-, -SH-, -OH- or -CONR⁵₂- substituted Si-C-bonded C_1 - C_{20} hydrocarbon radical or C_1 - C_{15} hydrocarbonoxy radical in which one or more nonadjacent methylene units may be replaced by groups -O-, -CO-, -COO-, -OCO-, -OCOO-, -S-, or -NR⁵- and in which one or more nonadjacent methine units may be replaced by groups -N=, -N=- or -P=,
- Is a hydrogen atom or a monovalent, optionally -CN-, -NCO-, -COOH-, -COOR 5 -, -halogen-, -acryloyl-, -SH-, -OH- or -CONR 5 ₂- substituted Si-C-bonded C₁-C₂₀ hydrocarbon radical or C₁-C₁₅ hydrocarbonoxy radical in which one or more nonadjacent methylene units may be replaced by groups -O-, -CO-, -COO-, -OCO-, -OCOO-, -S-, or -NR 5 and in which one or more nonadjacent methine units may be replaced by group, -N=, -N=- or -P=,
- R² is hydrogen or an optionally -CN- or halogen-substituted C₁-C₂₀ hydrocarbon radical,
- R^4 is hydrogen or an optionally -CN- or halogen-substituted C_1 - C_{20} hydrocarbon radical or a substituted or unsubstituted polyalkylene oxide having 1 to 4000 carbon atoms,
- R^5 is hydrogen or an optionally -CN- or halogen-substituted C_1 - C_{10} hydrocarbon radical,
- p is 0 or an integer from 1 to 100,000,
- q is 0 or an integer from 1 to 100,000,

f is 1, 2 or 3,

s is an integer which is at least 1 and

t is 0 or an integer which is at least 1,

p+q is an integer which is at least 1,

comprising reacting:

at least one silane of the formula

$$[(R^3O)_fR^1_{3-f}SiCR^2_2P(O)(OR^4)_2]$$
 [III]

is reacted with at least one silicon compound of the general formula

$$(R_2SiO_{2/2})_p(R_3SiO_{1/2})_q[O_{1/2}H]_m$$
 [IV]

where

 R^3 is hydrogen or an optionally -CN- or halogen-atom-substituted C_1 - C_{20} hydrocarbon radical, and

m is an integer 1 or 2.

the reaction taking place neat or in organic solvent.

- 7. (Previously Presented) The process of claim 6, wherein the sum p + q is an integer which is at least 2.
- 8. (Previously Presented) The process of claim 6, carried out in the presence of catalyst.
- 9. (Previously Presented) The process of claim 7, carried out in the presence of catalyst.
- 10. (Previously Presented) The process of claim 6, carried out at temperature(s) of 0 to 200°C.

S/N: 10/595,701 Reply to Office Action of June 11, 2008

- 11. (Previously Presented) The process of claim 7, carried out at temperature(s) of 0 to 200°C.
- 12. (Previously Presented) The process of claim 8, carried out at temperature(s) of 0 to $200^{\circ}C$.
- 13. (Previously Presented) The process of claim 6, carried out in an inert gas atmosphere.
- 14. (Previously Presented) The process of claim 7, carried out in an inert gas atmosphere.
- 15. (Previously Presented) The process of claim 8, carried out in an inert gas atmosphere.
- 16. (Previously Presented) The process of claim 10, carried out in an inert gas atmosphere.
- 17. (New) The process of claim 6, wherein the reaction takes place in an aprotic organic solvent.
- 18. (New) The process of claim 6, wherein the reaction takes place in the absence of a catalyst.
 - 19. (New) The process of claim 6, wherein the reaction takes place neat.
- 20. (New) The process of claim 6, wherein the reaction mixture is homogenous.